



## Correction: Atomic layer deposition of a MoS<sub>2</sub> film

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Correction for 'Atomic layer deposition of a MoS<sub>2</sub> film' by Lee Kheng Tan *et al.*, *Nanoscale*, 2014, **6**, 10584–10588.

(1) There is an error to the existing author list. The correct list should be:

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(2) There is an error in the Acknowledgements. It should read:

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The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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